

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	13	((plasma near3 (\$4cvd or (vapor adj deposit\$4))) or pecvd or pcvd or pacvd or (p adj cvd)) and (gas with introduc\$5 with (reactor or chamber) with (direction) with toward with (substrate or surface or object))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 13:58
L2	17	((plasma near3 (\$4cvd or (vapor adj deposit\$4))) or pecvd or pcvd or pacvd or (p adj cvd)) and (gas with introduc\$5 with (reactor or chamber) with (direction) with toward with (substrate or surface or object or wafer))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 15:10
L3	219	((plasma near3 (\$4cvd or (vapor adj deposit\$4))) or pecvd or pcvd or pacvd or (p adj cvd)) and ((gas or reactant or vapor) with (introduc\$5 or flow\$4) with (reactor or chamber) with (toward) with (substrate or surface or object or wafer))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 14:28
L4	32	((plasma near3 (\$4cvd or (vapor adj deposit\$4))) or pecvd or pcvd or pacvd or (p adj cvd)) same ((gas or reactant or vapor) with (introduc\$5 or flow\$4) with (reactor or chamber) with (toward) with (substrate or surface or object or wafer))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 14:01
L5	93	(ECR or cyclotron\$4) and ((gas or reactant or vapor) with (introduc\$5 or flow\$4) with (reactor or chamber) with (toward) with (substrate or surface or object or wafer))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 14:07
L6	148	((Yamazaki.in. or Inoue.in. or Miyanaga.in. or SEL.as. or (Semiconductor adj energy adj lab\$9)) and ((pulse or pulsed or pulsing or intermittent\$4 or intermittant\$4 or discontin\$8 or (on near2 off)) near3 (frequency of electromagnetic or microwave or rf or vhf or wave)) with (plasma or glow or discharge or ECR))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 14:10

L8	21	((Yamazaki.in. or Inoue.in. or Miyanaga.in. or SEL.as. or (Semiconductor adj energy adj lab\$9)) and ((pulse or pulsed or pulsing or intermittent\$4 or intermittant\$4 or discontin\$8 or (on near2 off)) near3 (frequency of electromagnetic or microwave or rf or vhf or wave)) with (plasma or glow or discharge or ECR) same (superpos\$8 or continuous\$6))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 14:11
L9	91	((Yamazaki.in. or Inoue.in. or Miyanaga.in. or SEL.as. or (Semiconductor adj energy adj lab\$9)) and ((pulse or pulsed or pulsing or intermittent\$4 or intermittant\$4 or discontin\$8 or (on near2 off)) near3 (frequency of electromagnetic or microwave or rf or vhf or wave)) with (coat\$4 or deposit\$4 or film or layer or \$4Cvd) same (superpos\$8 or continuous\$6))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 14:12
L10	85	(Yamazaki.in. or Inoue.in. or Miyanaga.in. or SEL.as. or (Semiconductor adj energy adj lab\$9)) and (((pulse or pulsed or pulsing or intermittent\$4 or intermittant\$4 or discontin\$8 or (on near2 off)) near3 (frequency of electromagnetic or microwave or rf or vhf or wave)) with ((continuous\$4) near3 (frequency of electromagnetic or microwave or rf or vhf or wave)) same (plasma or deposit\$4 or coat\$4 or film or layer or \$4cvd or glow or discharge))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 14:13
L12	5	(Yamazaki.in. or Inoue.in. or Miyanaga.in. or SEL.as. or (Semiconductor adj energy adj lab\$9)) and (((pulse or pulsed or pulsing or intermittent\$4 or intermittant\$4 or discontin\$8 or (on near2 off)) near3 (frequency of electromagnetic or microwave or rf or vhf or wave)) with ((continuous\$4) near3 (frequency of electromagnetic or microwave or rf or vhf or wave)) same (plasma or deposit\$4 or coat\$4 or film or layer or \$4cvd or glow or discharge) same superpos\$10)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 14:15

L13	7070	(427/569,570,571,572,574,575, 578,582,583,584,248.1,255.23, 255.28,250,255.31,255.36,255. 391,255.392,255.393).CCLS.	US-PGPUB; USPAT	OR	OFF	2005/06/24 14:15
L14	1452	(118/723R,723MP,723MW, 723MA).CCLS.	US-PGPUB; USPAT	OR	OFF	2005/06/24 14:15
L15	7070	(427/569,570,571,572,574,575, 578,582,583,584,248.1,255.23, 255.28,250,255.31,255.36,255. 391,255.392,255.393).CCLS.	US-PGPUB; USPAT	OR	OFF	2005/06/24 14:15
L16	1452	(118/723R,723MP,723MW, 723MA).CCLS.	US-PGPUB; USPAT	OR	OFF	2005/06/24 14:15
L17	8256	L15 or L16	US-PGPUB; USPAT	OR	ON	2005/06/24 14:16
L18	303	427/571.ccls.	US-PGPUB; USPAT	OR	ON	2005/06/24 14:16
L19	13	((plasma near3 (\$4cvd or (vapor adj deposit\$4))) or pecvd or pcvd or pacvd or (p adj cvd)) and ((gas or reactant or vapor) with (introduc\$5 or flow\$4) with (reactor or chamber) with (toward or direct\$5) with (substrate or surface or object or wafer) with (prefer\$8 or advantag\$7 or benefi\$9))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 14:30
L20	6	L16 and (gas with introduc\$5 with (reactor or chamber) with (direction) with toward with (substrate or surface or object or wafer))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 14:31
L21	19	L17 and (gas with introduc\$5 with (reactor or chamber) with (direction) with toward with (substrate or surface or object or wafer))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 14:31
L22	38	(((\$4cvd or (vapor adj deposit\$4))) or pecvd or pcvd or pacvd or (p adj cvd)) and (gas with introduc\$5 with (reactor or chamber) with (direction) with toward with (substrate or surface or object or wafer))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 15:11
L23	31	L22 not L4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 15:11

L24	21	L22 not L2	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 15:11
L27	8256	L15 or L16	US-PGPUB; USPAT	OR	ON	2005/06/24 15:14
L28	236	L27 and (((pulse or pulsed or pulsing or intermittent\$4 or intermittant\$4 or discontin\$8 or (on near2 off)) near3 (frequency of electromagnetic or microwave or rf or vhf or wave)) with (plasma or glow or discharge or ECR))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 15:15
L29	35	L27 and (((pulse or pulsed or pulsing or intermittent\$4 or intermittant\$4 or discontin\$8 or (on near2 off)) near3 (frequency of electromagnetic or microwave or rf or vhf or wave)) with (coat\$4 or deposit\$4 or film or layer or \$4Cvd) with (superpos\$8 or continuous\$6))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 15:17
L30	49	L27 and (((pulse or pulsed or pulsing or intermittent\$4 or intermittant\$4 or discontin\$8 or (on near2 off)) near3 (frequency of electromagnetic or microwave or rf or vhf or wave)) with ((continuous\$4) near3 (frequency of electromagnetic or microwave or rf or vhf or wave)) same (plasma or deposit\$4 or coat\$4 or film or layer or \$4cvd or glow or discharge))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 15:18
L31	4	L27 and (((pulse or pulsed or pulsing or intermittent\$4 or intermittant\$4 or discontin\$8 or (on near2 off)) near3 (frequency of electromagnetic or microwave or rf or vhf or wave)) with ((continuous\$4) near3 (frequency of electromagnetic or microwave or rf or vhf or wave)) same (plasma or deposit\$4 or coat\$4 or film or layer or \$4cvd or glow or discharge) same (superpos\$8 or overlap\$8 or onto or simultaneous\$7 or "same time"))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 15:18

L32	8	(((pulse or pulsed or pulsing or intermittent\$4 or intermittant\$4 or discontin\$8 or (on near2 off)) near3 (frequency of electromagnetic or microwave or rf or vhf or wave)) with ((continuous\$4) near3 (frequency of electromagnetic or microwave or rf or vhf or wave)) same (plasma or glow or discharge or PEcvd) same (superpos\$8 or overlap\$8 or onto or simultaneous\$7 or "same time") same (deposit\$4 or coat\$4 or film or layer or \$4cvd))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 15:19
L33	87	(((pulse or pulsed or pulsing or intermittent\$4 or intermittant\$4 or discontin\$8 or (on near2 off)) near3 (frequency of electromagnetic or microwave or rf or vhf or wave)) with ((continuous\$4) near3 (frequency of electromagnetic or microwave or rf or vhf or wave)) same (plasma or glow or discharge or PEcvd) same (deposit\$4 or coat\$4 or film or layer or \$4cvd))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 15:19
L34	87	(((pulse or pulsed or pulsing or intermittent\$4 or intermittant\$4 or discontin\$8 or (on near2 off)) near3 (frequency of electromagnetic or microwave or rf or vhf or wave)) with ((continuous\$4) near3 (frequency of electromagnetic or microwave or rf or vhf or wave)) same (plasma or glow or discharge or PEcvd) same (deposit\$4 or coat\$4 or film or layer or \$4cvd))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 15:20
L35	103	(((pulse or pulsed or pulsing or intermittent\$4 or intermittant\$4 or discontin\$8 or (on near2 off)) near3 (frequency of electromagnetic or microwave or rf or vhf or wave)) same ((continuous\$4) near3 (frequency of electromagnetic or microwave or rf or vhf or wave)) same (plasma or glow or discharge or PEcvd) same (deposit\$4 or coat\$4 or film or layer or \$4cvd))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 15:20

L36	16	L35 not L34	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 15:20
L38	21	((pulse or pulsed or pulsing or intermittent\$4 or intermittant\$4 or discontin\$8 or (on near2 off)) with (frequency of electromagnetic or microwave or rf or vhf or wave)) with ((continuous\$4) with (superpos\$8 or overlap\$8 or combin\$7 or onto or simultaneous\$4 or "same time" or concurrent\$4)) same (plasma or glow or discharge or PEcvd) same (deposit\$4 or coat\$4 or film or layer or \$4cvd))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 15:21
L39	81	((pulse or pulsed or pulsing or intermittent\$4 or intermittant\$4 or discontin\$8 or (on near2 off)) near3 (frequency of electromagnetic or microwave or rf or vhf or wave)) same ((continuous\$4) near3 (frequency of electromagnetic or microwave or rf or vhf or wave)) same (plasma or glow or discharge or PEcvd) same (power or frequency) same (deposit\$4 or coat\$4 or film or layer or \$4cvd))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 15:21
L40	156	((pulse or pulsed or pulsing or intermittent\$4 or intermittant\$4 or discontin\$8 or (on near2 off)) near3 (frequency of electromagnetic or microwave or rf or vhf or wave)) same ((continuous\$4) near3 (frequency of electromagnetic or microwave or rf or vhf or wave)) same (plasma or glow or discharge or PEcvd)) and ((metal\$2 or tungsten or ceramic or insulating or titanium or molybdenum or Ti or W or Mo or silicide) with (deposit\$4 or coat\$4 or film or layer or \$4cvd))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/06/24 15:22